

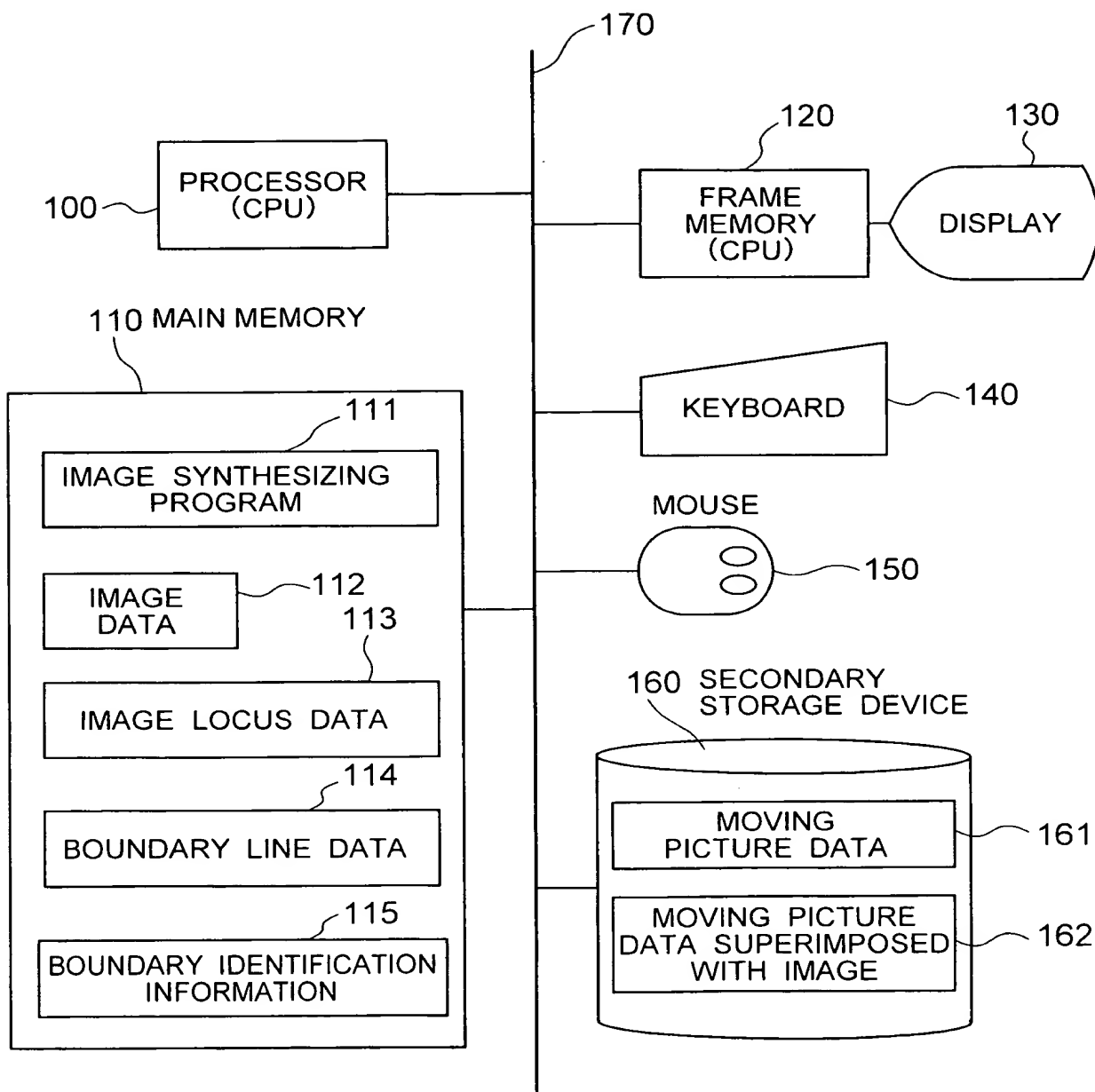
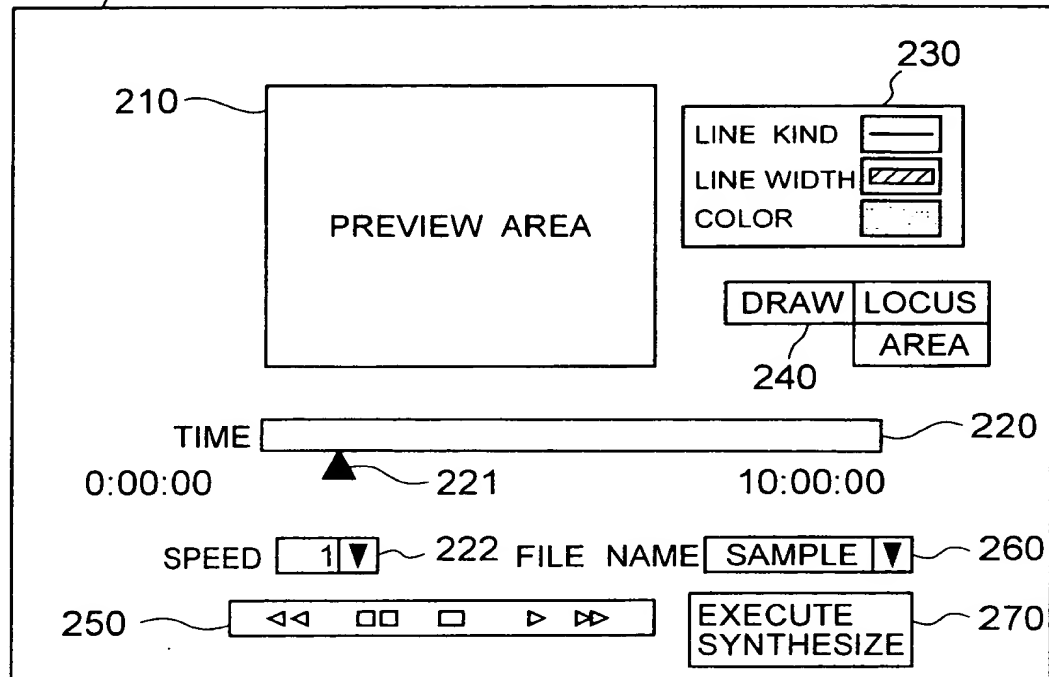
[illegible]

FIG. 2

200 IMAGE SYNTHESIZING PROGRAM VIEW



000000" 850T5950

FIG. 3

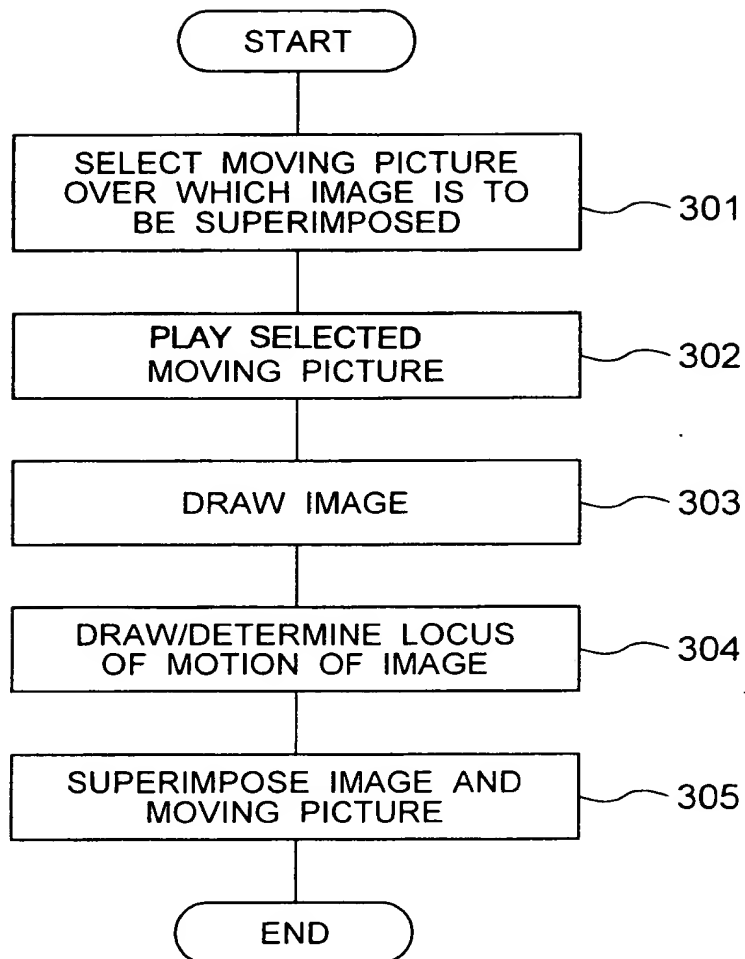


FIG. 5

200 IMAGE SYNTHESIZING PROGRAM VIEW

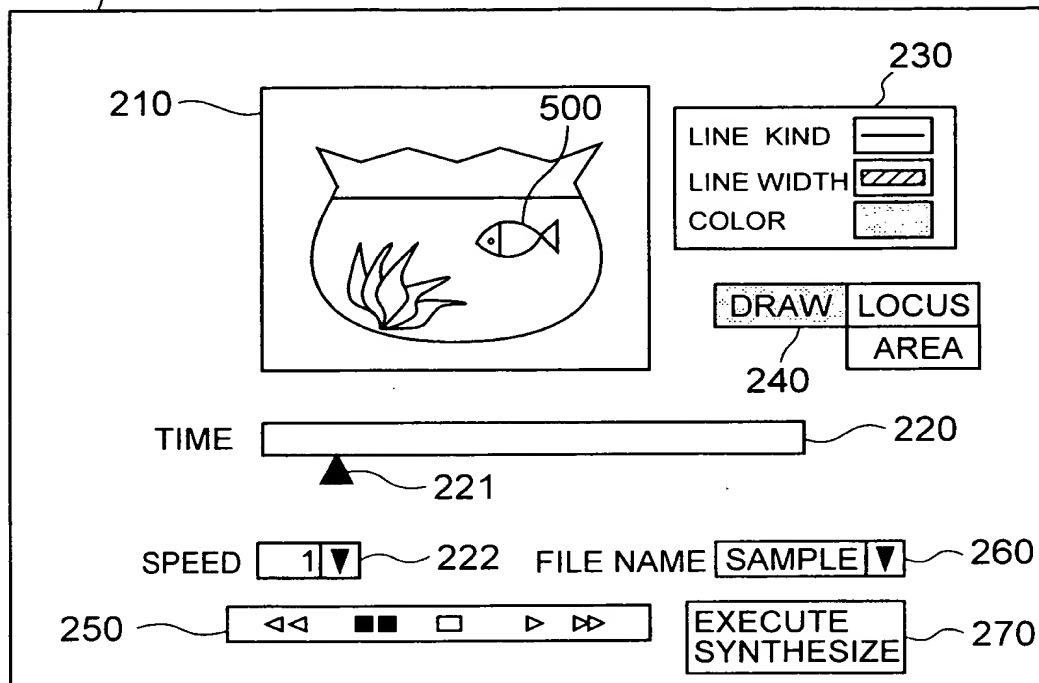
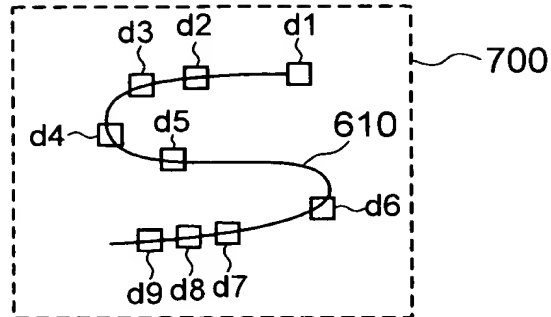
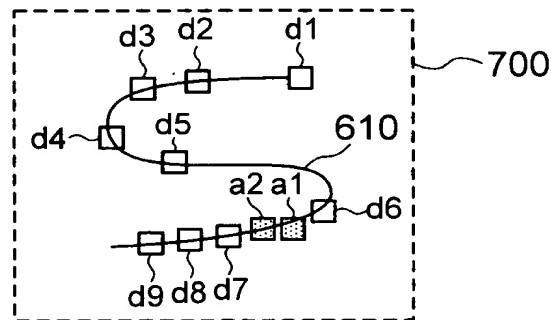


FIG. 7

BEFORE
MODIFICATION



ADDED



DELETED

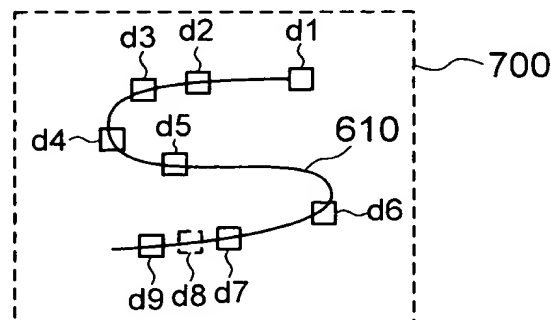


FIG. 8 A

800

POINT	TIME	POSITION	SIZE	DIRECTION	TRANSMITTIVITY
d1	0:00:10:00	(240,100)	1	0°	0
d2	0:00:11:00	(235,105)	1	0°	0
d3	0:00:12:00	(210,110)	1	15°	0
d4	0:00:13:00	(190,130)	1	0°	0
d5	0:00:14:00	(235,150)	1	180°	0
d6	0:00:15:00	(280,200)	1	180°	0
d7	0:00:16:00	(210,250)	1	15°	0
d8	0:00:17:00	(195,255)	1	15°	0
d9	0:00:18:00	(180,255)	1	0°	0

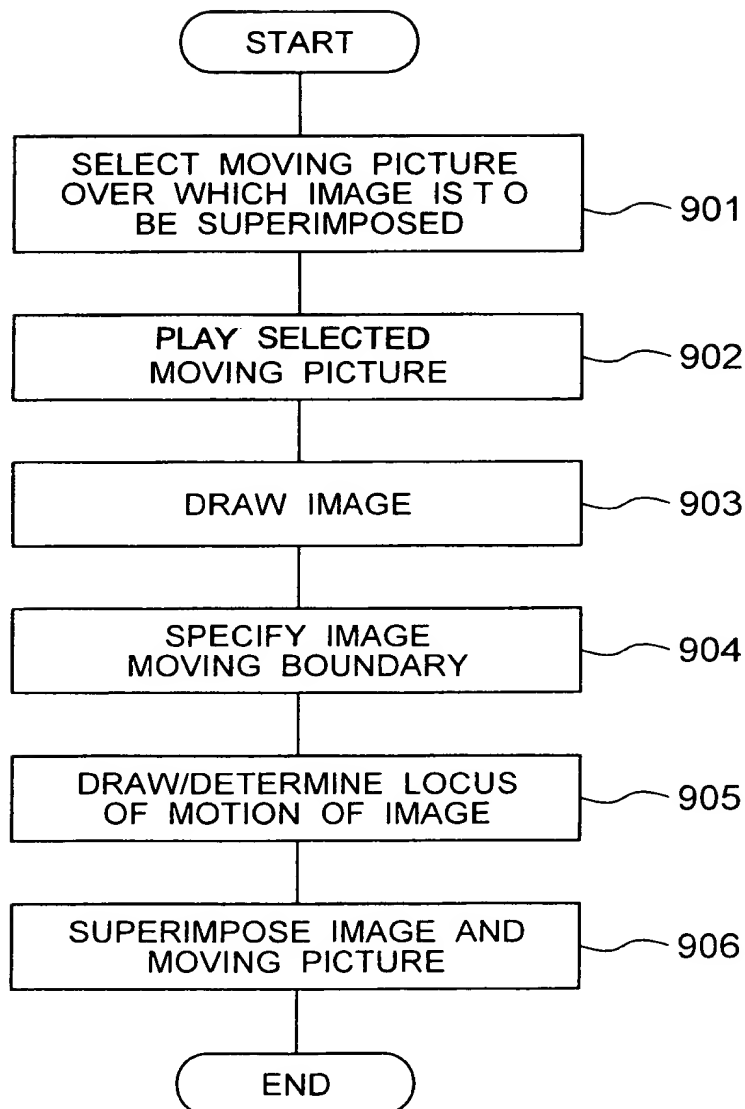
FIG. 8 B

POINT	TIME	POSITION			
d1	0:00:10:00	(240,100)			
⋮	⋮	⋮			
d6	0:00:15:00	(240,100)			
a1	0:00:16:00	(280,200)			
a2	0:00:17:00	(240,230)			
d7	0:00:18:00	(210,250)			
⋮	⋮	⋮			

FIG. 8 C

POINT	TIME	POSITION			
d1	0:00:10:00	(240,100)			
⋮	⋮	⋮			
d6	0:00:15:00	(240,100)			
d7	0:00:16:00	(210,250)			
d9	0:00:17:00	(180,255)			

FIG. 9



0564096-063000

FIG. 10

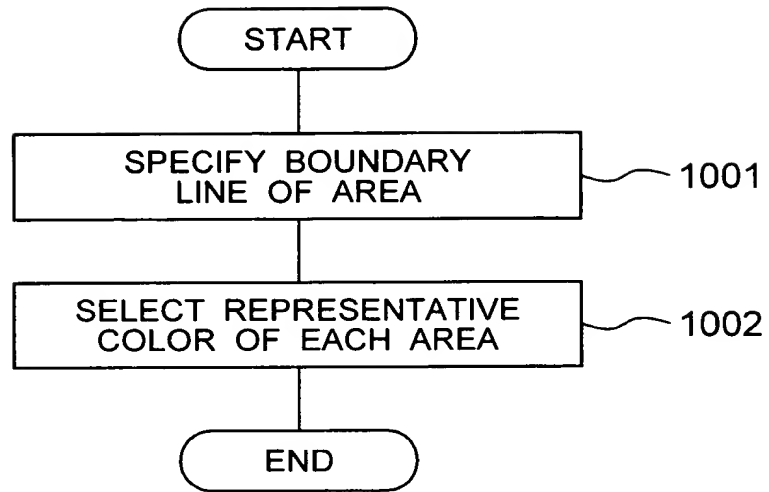


FIG. 11

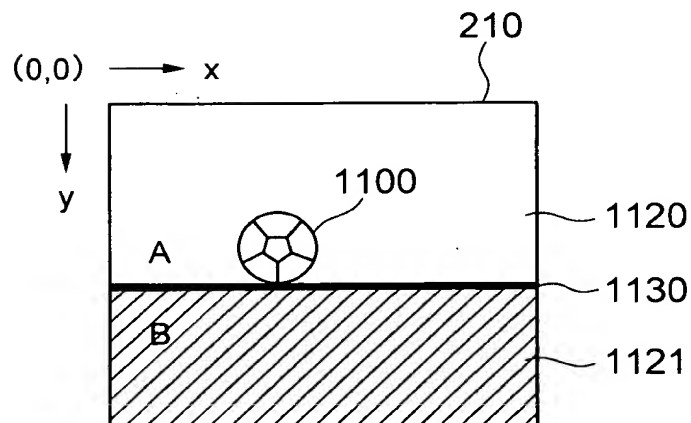


FIG. 13

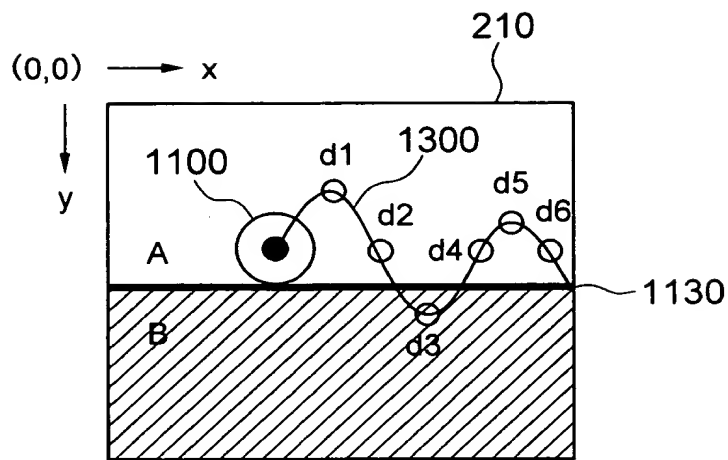
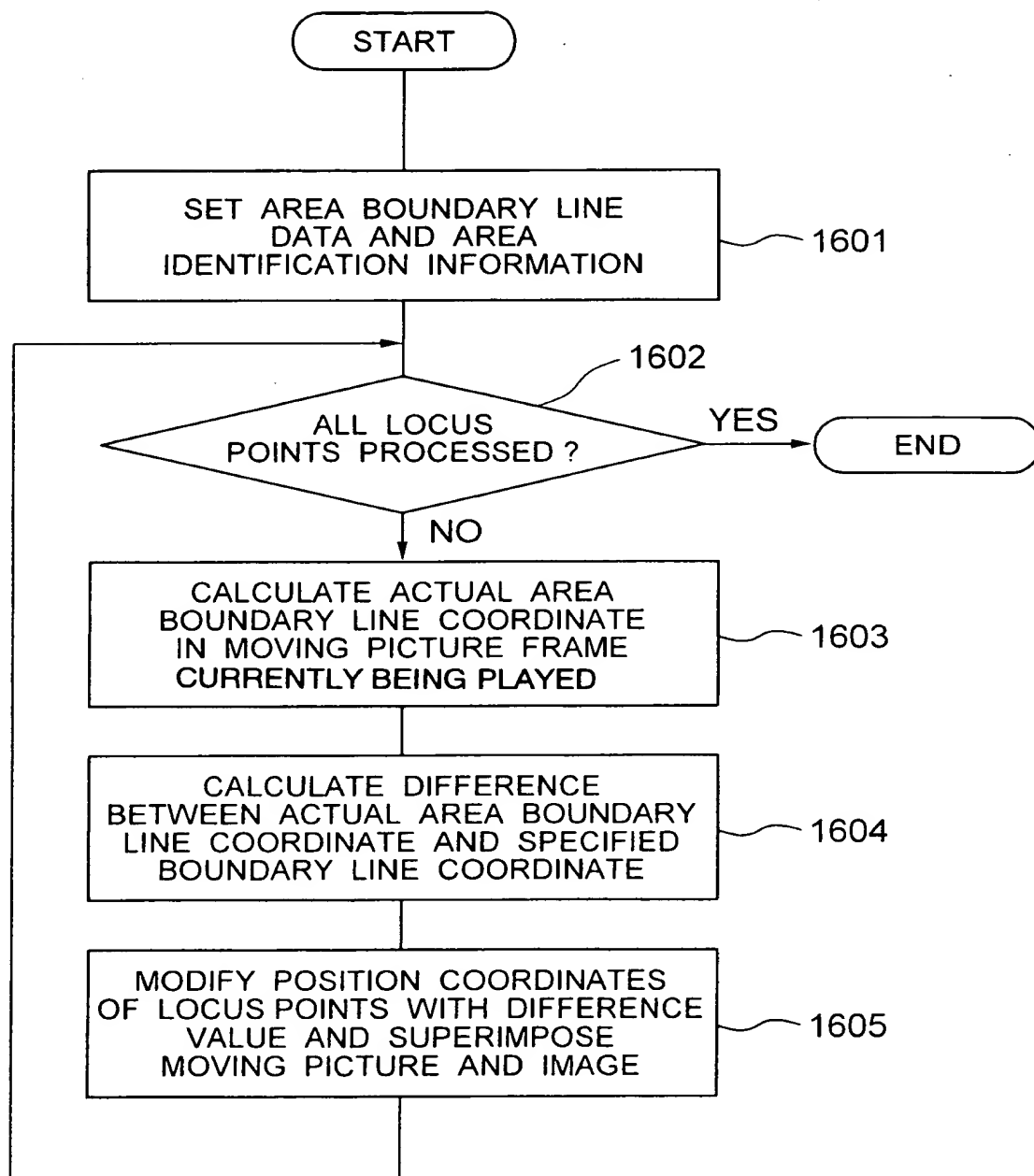


FIG. 14

x	0		130	170	190	250		280	340	350
y	180		175	165	175	170		183	189	185

POINT	TIME	POSITION
d1	0:00:10:00	(130,170)
d2	0:00:11:00	(170,100)
d3	0:00:12:00	(190,100)
d4	0:00:13:00	(250,210)
d5	0:00:14:00	(280,160)
d6	0:00:15:00	(340,170)
d7	0:00:16:00	(350,175)

FIG. 16



A cross-sectional view of a device structure 210. The structure consists of a substrate 1130 (hatched) and a layer 1710 (solid) on top of it. A layer 1100 is formed on the surface of layer 1710, and a layer 1300 is formed on top of layer 1100. A coordinate system is shown with the origin (0,0) at the top-left corner, the x-axis pointing right, and the y-axis pointing down. A dimension d is indicated as the thickness of layer 1710. A point A is marked on the surface of layer 1100.

A cross-sectional view of a semiconductor device. A substrate 210 is shown with a patterned layer 1100 on its top surface. The patterned layer 1100 has a central circular feature 1300 and several smaller circular features. A horizontal line 1710 is drawn across the device, and a dashed line 1130 is shown below it. The region between 1710 and 1130 is labeled B. The region above 1710 is labeled A. A coordinate system is shown with the origin (0,0) at the top left, the x-axis pointing right, and the y-axis pointing down. A dimension d is indicated between the horizontal line 1710 and the dashed line 1130.